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CERTIFICATE OF MAILING

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Signature: _____

Rebecca A. Baumann

PATENT

Attorney Docket No. NTI-025

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application)

PATENT APPLICATION

Inventor(s): Chi-Ming Tsai)

Art Unit: 2123

Application No.: 10/025,414)

Examiner: unknown

Filed: 12/18/2001)

Title "Method For Providing Flexible And Dynamic
Reporting Capability Using Simulation Tools")

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AUG 26 2002

Technology Center 2100

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Listed below or on an attached Form PTO-1449 is information known to applicant(s). A copy of each listed publication and U.S. and foreign patent, except for pending U.S. applications, is being submitted herewith, along with a concise explanation of information in a foreign language, if any, pursuant to 37 C.F.R. §1.97-1.98.

Applicants respectfully request that the listed information be considered by the Examiner and be made of record in the above-identified application. If form PTO-1449 is enclosed, the Examiner is requested to initial and return it in accordance with MPEP § 609.

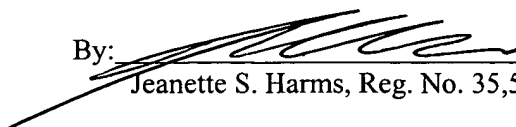
This statement is not intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56.

- ☒ This statement qualifies under 37 C.F.R. § 1.97, subsection (b) because (check all that apply):
- ☐ (1) It is being filed within 3 months of the application filing date and is other than a continued prosecution application under § 1.53(d)
-- OR --
 - ☐ (2) It is being filed within 3 months of entry of a national stage
-- OR --
 - ☒ (3) It is being filed before the mail date of the first Office Action on the merits.
-- OR --
 - ☐ (4) It is being filed before the mailing of a first Office Action after the filing of a request for continued examination under § 1.114
- ☐ 37 C.F.R. § 1.97(c). If this statement is being filed after the period specified in § 1.97(b), but before the mailing date of the earlier of a final office action under § 1.113, a notice of allowance under § 1.311, or an action that otherwise closes prosecution in the application, then:
- ☐ a certification as specified in § 1.97(e) is provided below; **or**
 - ☐ a fee of \$180.00 as set forth in § 1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.
- ☐ 37 C.F.R. § 1.97(d). If this statement is being filed after the period specified in § 1.97(c), but on or before payment of the issue fee, then:
- A. a certification as specified in § 1.97(e) is completed below; **and**
 - B. a fee of \$180.00 as set forth in § 1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.
- ☒ **Fee Authorization.** The Commissioner is hereby authorized to charge any additional fees or credit any overpayment associated with this communication to Deposit Account No. 50-0574 (Docket No. NTI-025).

Respectfully submitted,

BEVER, HOFFMAN & HARMS, LLP

Dated: 8-19-02

By: 
Jeanette S. Harms, Reg. No. 35,537

Telephone: (408) 451-5907
Customer No. 29477

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|---|--|--------------------------------------|
| INFORMATION DISCLOSURE CITATION PTO-1449 | Atty. Docket No. NTI-025 | Serial No. 10/025,414-4802 |
| | Applicant TSAI, Chi-Ming | Group 2123 |
| Filing Date 12/18/2001 | RECEIVED AUG 26 2002 Technology Center 2100 | |



U.S. PATENT DOCUMENTS

| EXAMINER'S INITIALS | PATENT NO. | DATE | NAME | CLASS | SUBCLASS | FILING DATE |
|------------------------|------------|-----------|---------------|-------|----------|----------------|
| | 5,801,954 | 9/1/1998 | Le, et al. | 364 | 488 | 4/24/1996 |
| | 6,081,659 | 6/27/2000 | Garza, et al. | 395 | 500.22 | 4/26/1999 |

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Date Considered: _____

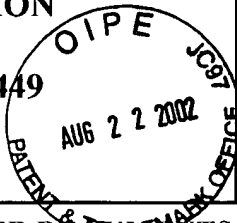
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

| INFORMATION DISCLOSURE CITATION TYPE PTO-1449 | | Atty. Docket No. NTI-025 Applicant TSAI, Chi-Ming Filing Date 12/18/2001 | | Serial No. 10/025,414-4802 Group 2123 | | RECEIVED AUG 26 2002 Technology Center 2100 | |
|--|----------------|--|---------|--|----------|--|--------------------------|
| FOREIGN PATENT DOCUMENTS | | | | | | | |
| EXAMINER'S INITIALS | PATENT NO. | DATE | COUNTRY | CLASS | SUBCLASS | TRANSLATION | |
| | | | | | | YES | NO |
| | WO 00/67075 A1 | 11/9/2000 | WO | | | <input type="checkbox"/> | <input type="checkbox"/> |
| | WO 00/67076 A1 | 11/9/2000 | WO | | | <input type="checkbox"/> | <input type="checkbox"/> |
| | WO 99/14638 A1 | 3/25/1999 | WO | | | <input type="checkbox"/> | <input type="checkbox"/> |

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|---|---|------------------------------------|--|
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| | | Applicant TSAI, Chi-Ming | Group 2123 |
|  | | Filing Date 12/18/2001 | RECEIVED AUG 26 2002 Technology Center 2100 |
| OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) | | | |
| EXAMINER'S INITIALS | CITATION | | |
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| | Gordon, R., et al., "Design and Analysis of Manufacturable Alternating Phase-Shifting Masks", Bacus News, Vol. 14, Issue 12, pp. 1-9, December 1998. | | |
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